
Scanning Micro-interferometer Array with Sub-picometer Resolution for MEMS Inspection

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Outline

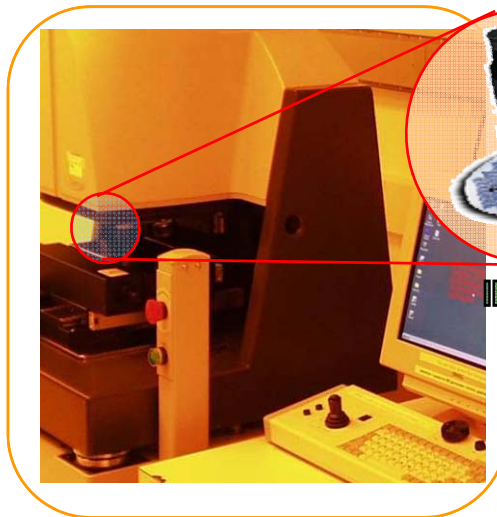
- Motivation
- Introduction to micro scanning grating interferometer (μ SGI)
- Fabrication of tunable gratings
- Active tuning of grating
- Demonstration of array operation of μ SGIs
- Conclusions and future work

Motivation

Lack of in-line metrology is a barrier in development of MEMS¹

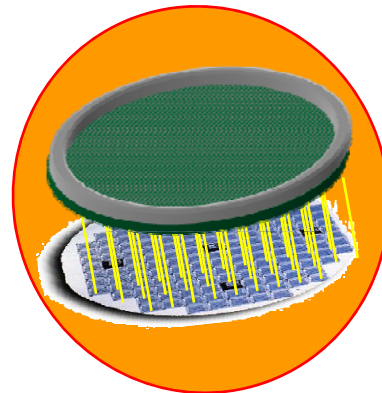
- MEMS inspection required for accurate fabrication
- Batch fabrication
- Metrology tools limited to small area inspection

Current Solution



Desired Solution

Array of miniaturized sensors testing in parallel

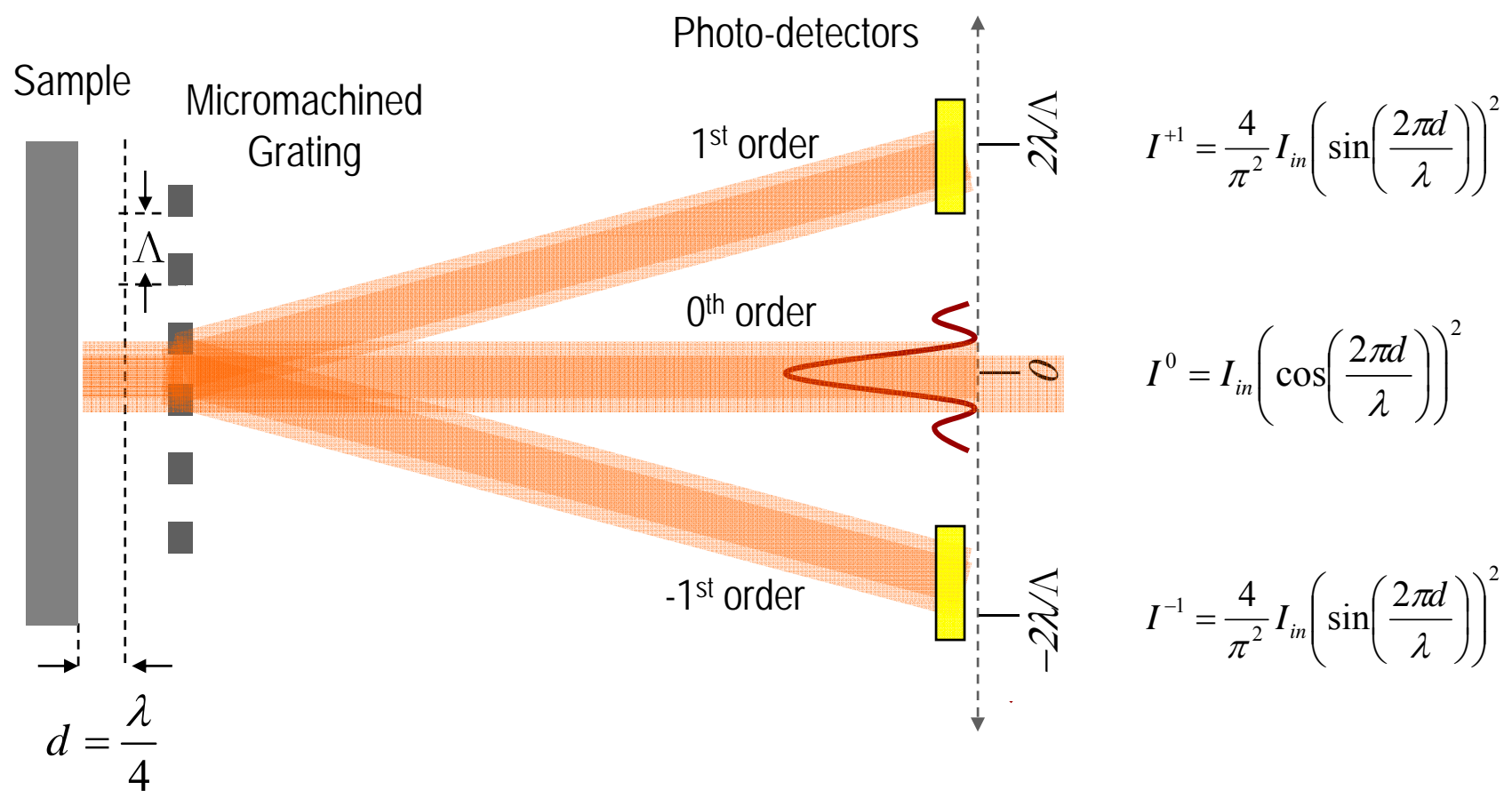


Desired characteristics

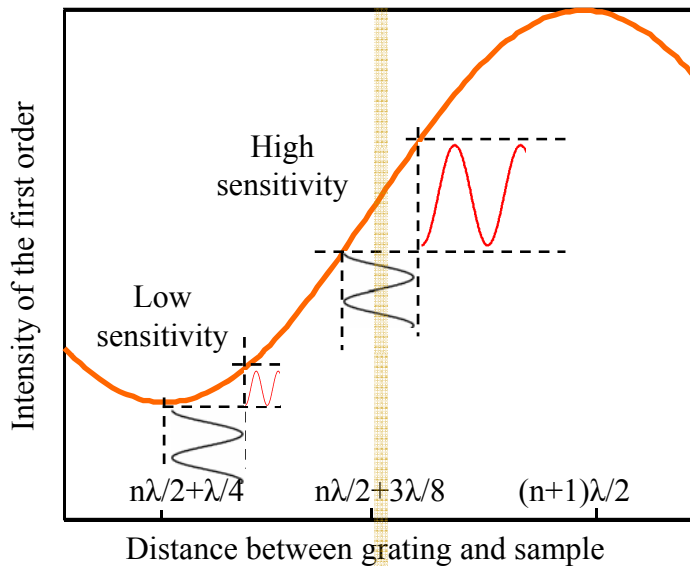
- Array operation
- Fast
- Dynamic metrology
- High resolution
- Non-contact

¹Panetta et al., Proceedings of ITC International Test Conference, 3-5 October, 2000, 1130-1135

Grating interferometer for miniaturization



Non-linearity in interferometers

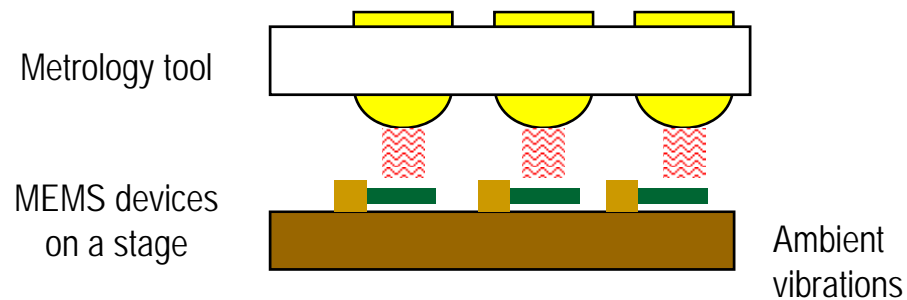


Grating

Sample

- Sensitivity of the interferometer changes depending on the position on the optical curve.
- At the saddle point sensitivity is high and the optical curve is linear.
- This is desired position of operation for high resolution metrology.

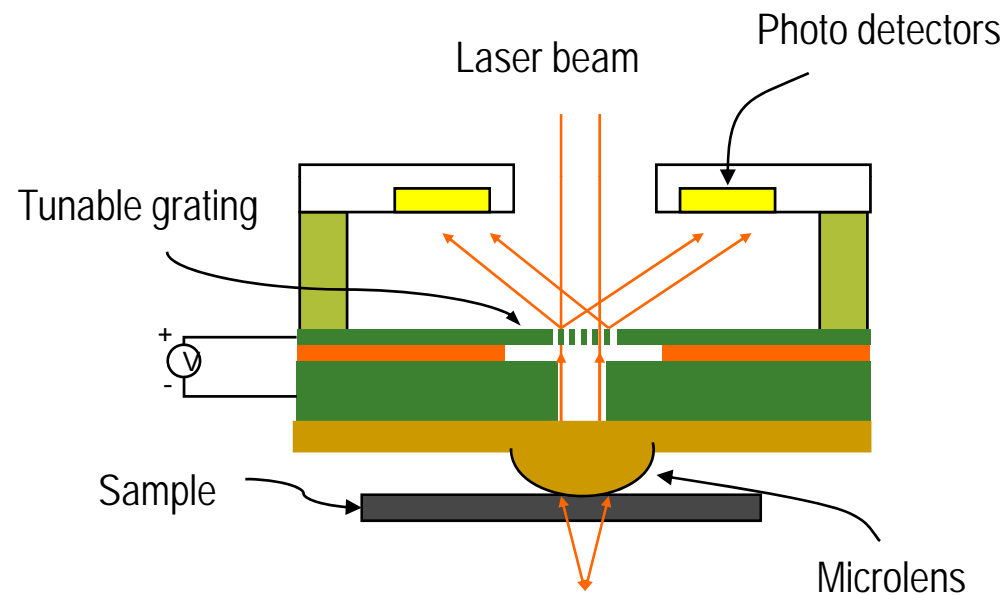
Need for active surface tracking in array operation



Schematic of parallel
Operation of μ SGI

- The micro-interferometer array needs to actively tune the distance between sample and each of the gratings for maximum sensitivity.
- Error in initial positioning, scanning a sample with tilt, ambient vibrations can cause change in position (Freq < 1kHz)
- Dynamic motions of MEMS under observation are at higher frequencies.

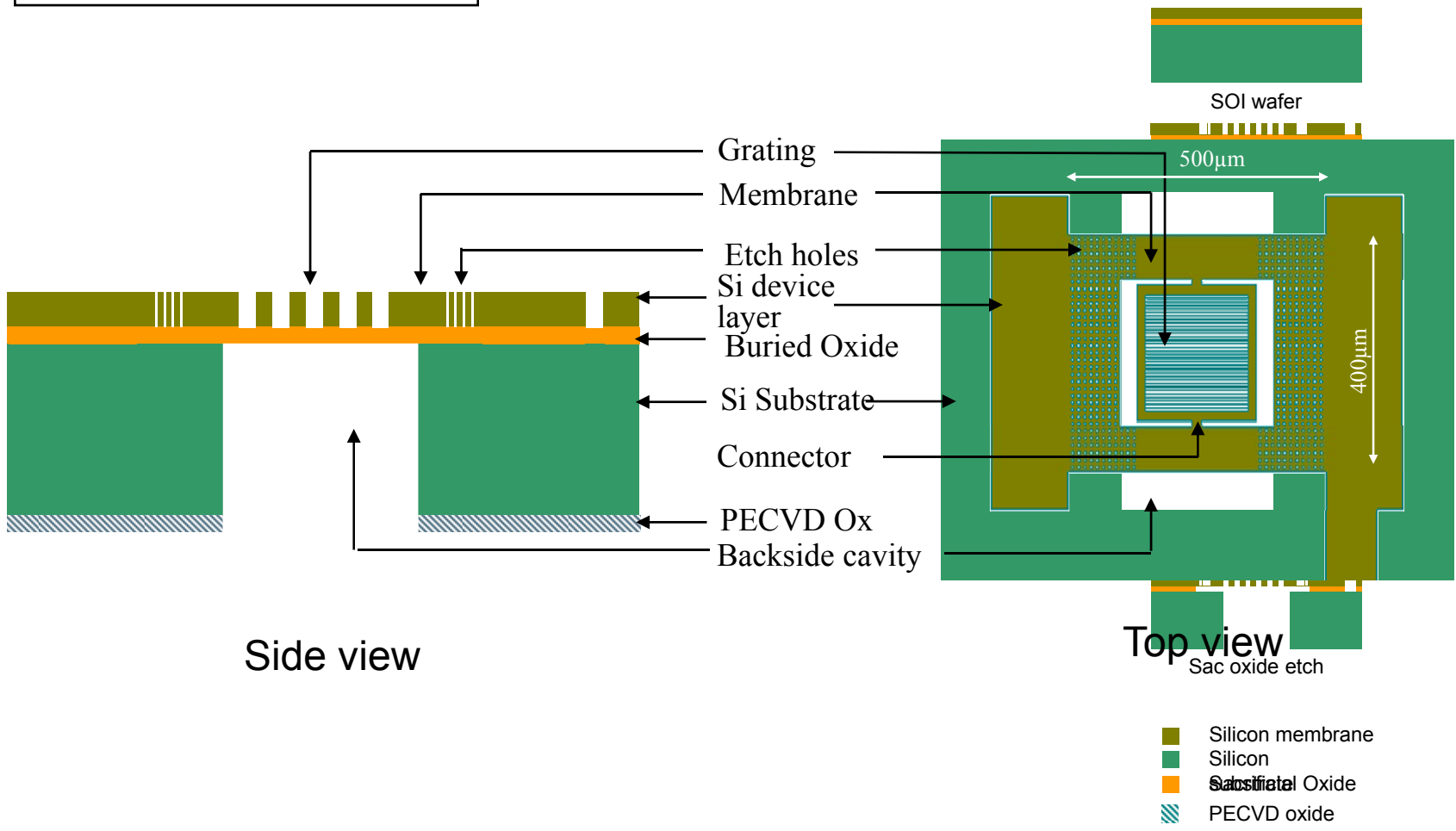
Micro scanning grating interferometer (μ SGI)



Schematic of μ SGI
(Miniaturized assembly)

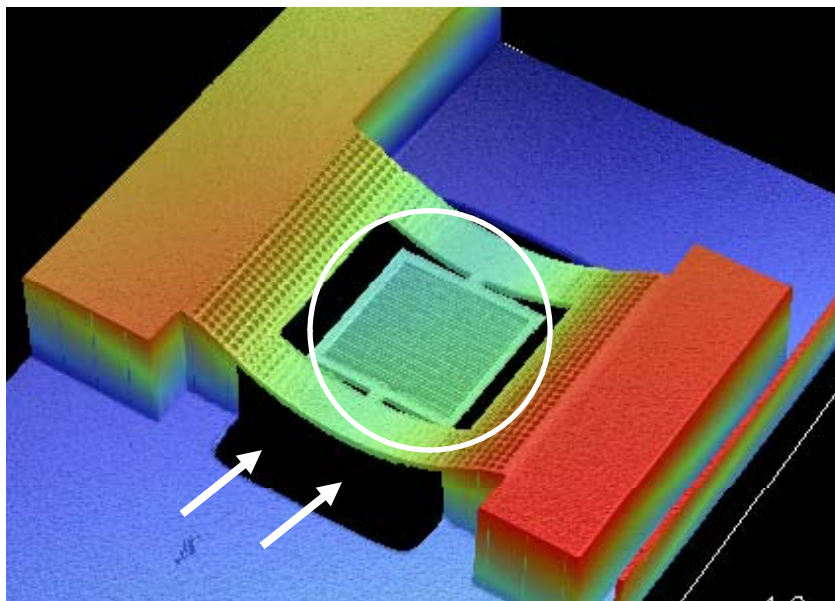
Fabrication of the μ SGI tunable gratings

Simple 2 mask process

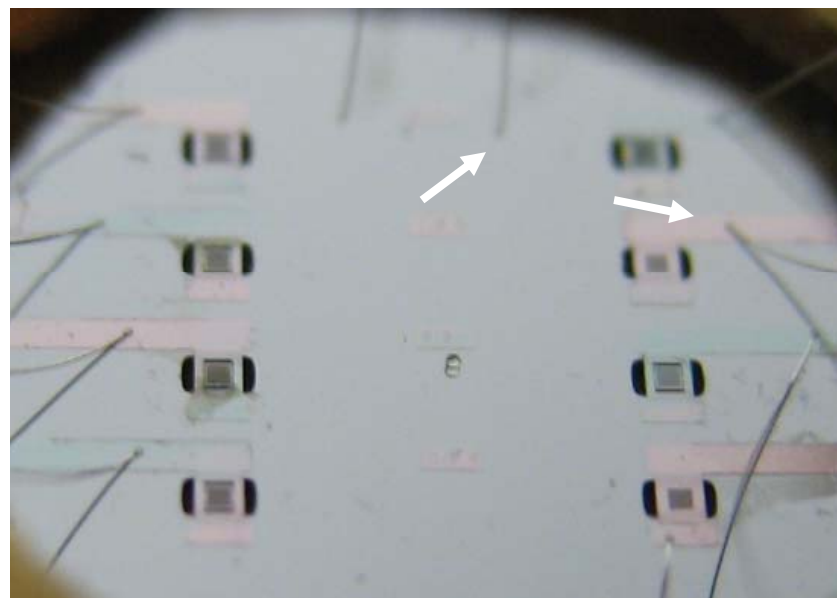


Fabrication results

- Flat grating – good optical performance
- Backside cavity – low squeezed film damping, no optical interaction with substrate
- Conductive Silicon – avoids metal electrodes, simple fabrication
- Gratings show 500nm range and 50kHz bandwidth

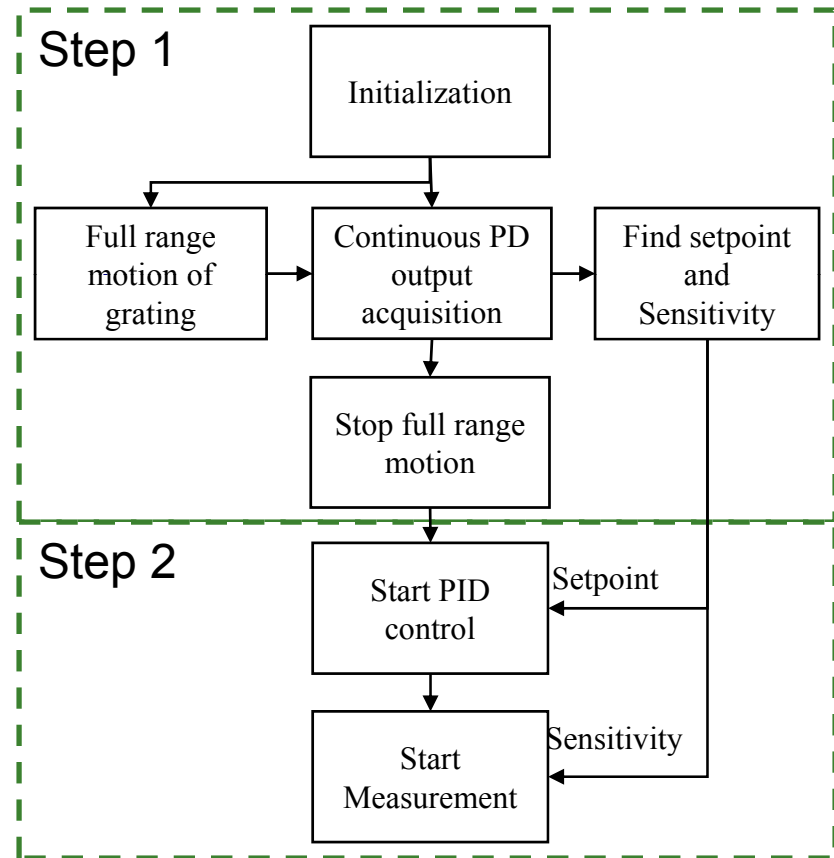
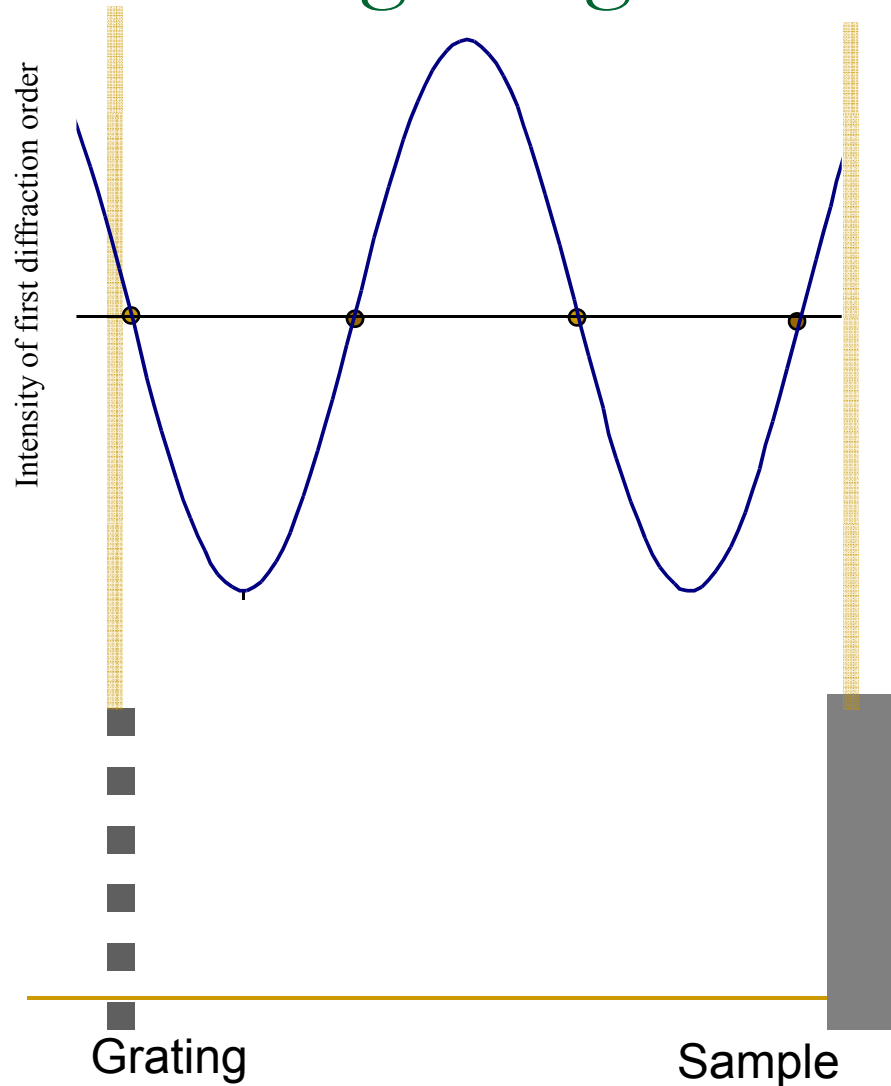


Electrostatically actuated tunable grating

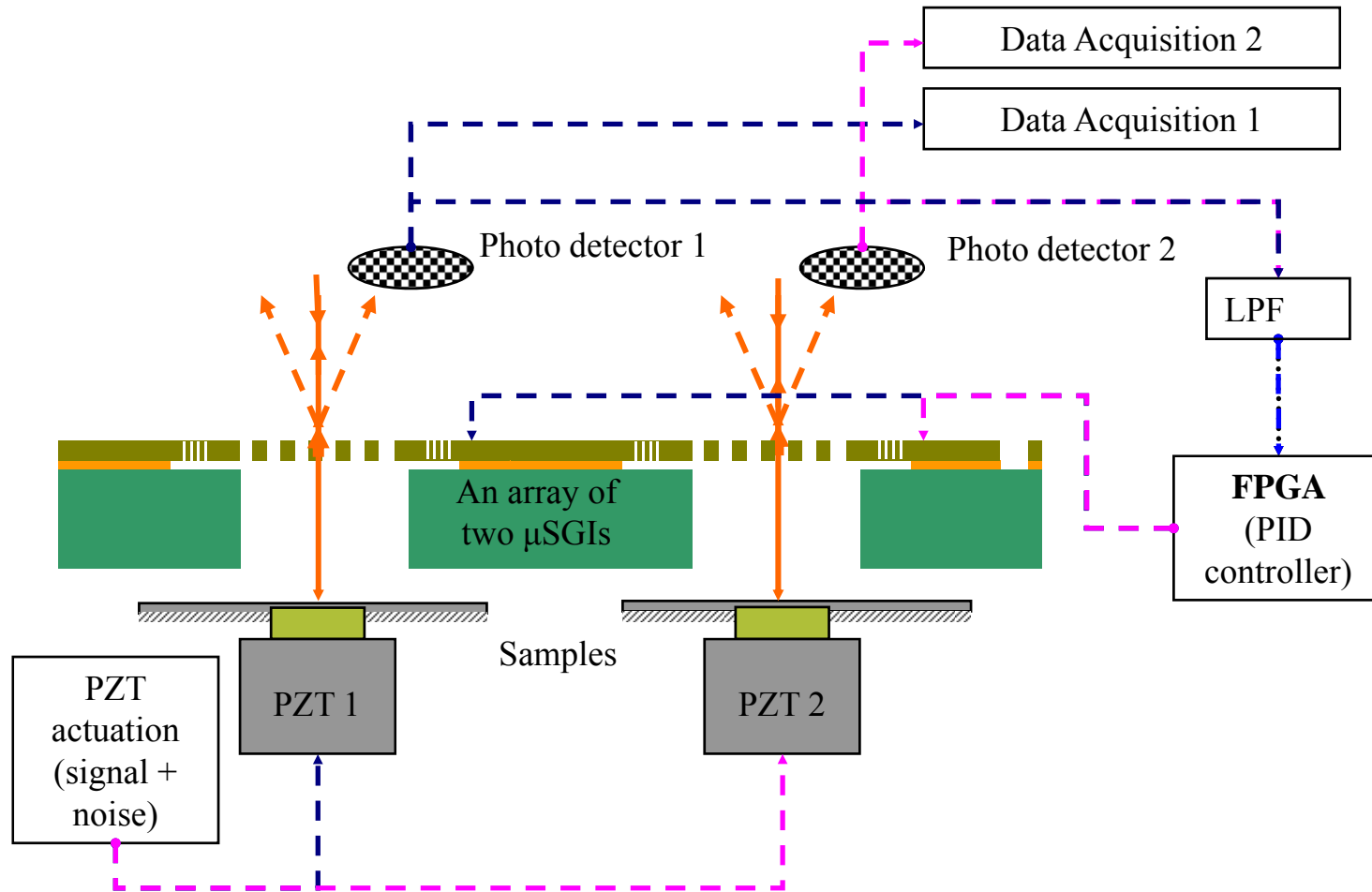


Array of tunable gratings fabricated on a chip and wire-bonds to the electrodes

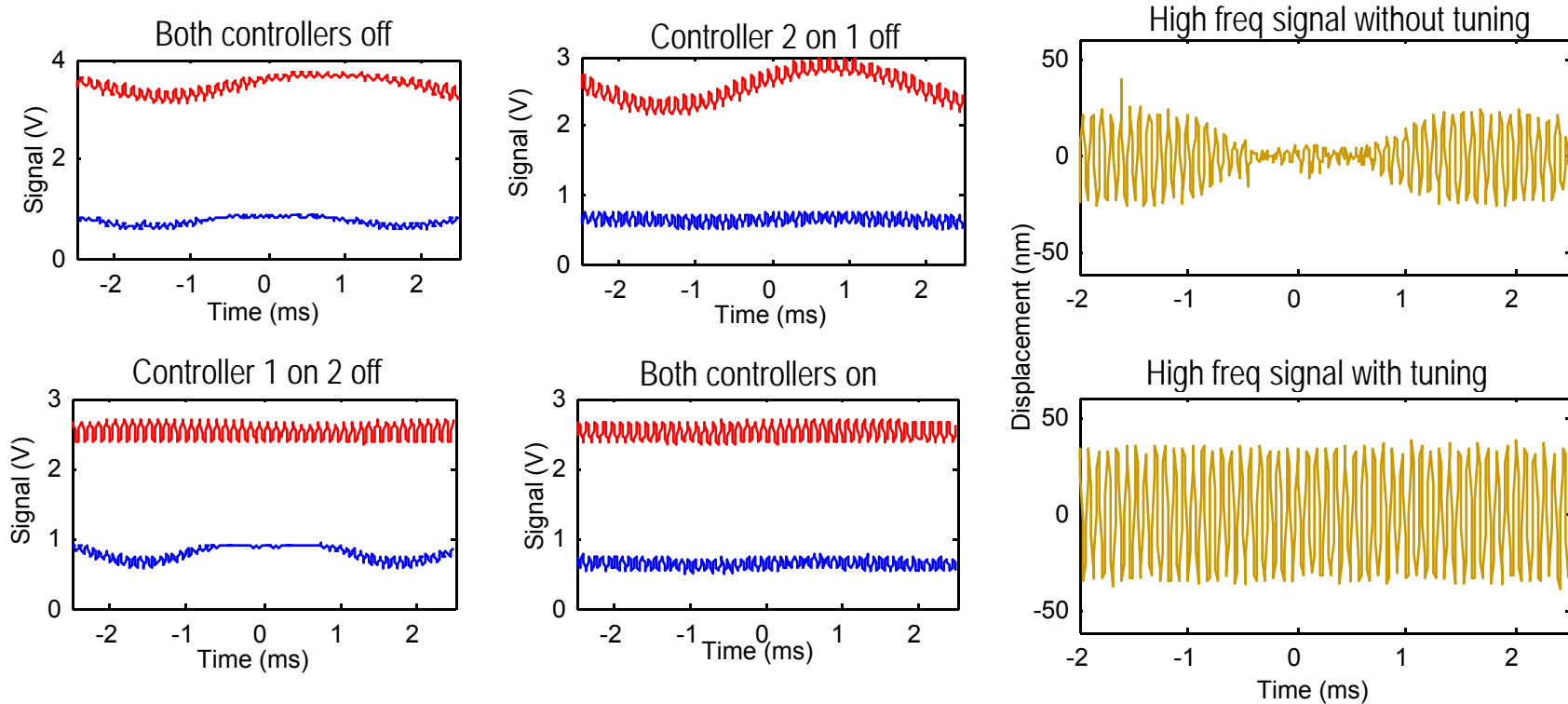
Active surface tracking algorithm for the tunable grating



Experimental setup for array operation



Array operation results



Demonstrates

- Independent, parallel, simultaneous operation
- Active surface tracking at $\sim 100\text{Hz}$
- Sub-picometer resolution

Conclusion

- The μ SGL technology may have significant impact on the growth of MEMS
- Tunable gratings fabricated in SOI substrate
- Active tuning algorithm developed and run in parallel on an FPGA
- Array operation of μ SGLs demonstrated
- Future work –
 - Non-linearities in control
 - miniaturization of optical source
 - Lens, photo-detector and source integration

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